

Sheet 1 of 1		INFORMATION DISCLOSURE STATEMENT					
FORM PTO/SB/08 A&B (<i>modified</i>) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (<i>Use several sheets if necessary</i>) Date Submitted to PTO: March 22, 2011				ATTY DOCKET NO. 2003_1187A		SERIAL NO. 10/644,738	
				APPLICANT Tsuyoshi NAKAMURA et al.			
				FILING DATE August 21, 2003		GROUP 1795	
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	BA						
	BB						
	BC						
	BD						
	BE						
OTHER DOCUMENT(S) (<i>Including Author, Title, Date, Pertinent Pages, Etc.</i>)							
	CA	T. Kijima et al., "Low Temperature Deposition of Bi ₄ Ti ₃ O ₁₂ Thin Films by MOCVD", Functional Devices Lab. Sharp Corp., with "Concise Explanation of the Relevance with Respect to Extended Abstracts (The 42nd Spring Meeting, 1995); The Japan Society of Applied Physics and Related Societies", 29p-D-2.					
	CB	H. Watanabe et al., "Development of Y1 Materials (Bi Layer Structured Ferroelectrics) Thin-Film Capacitors (II)", Olympus Optical Co., Ltd. *Symetrix Co., with "Concise Explanation of the Relevance with Respect to Extended Abstracts (The 55th Autumn Meeting, 1994); The Japan Society of Applied Physics", 20p-M-19.					
	CC	Jun-Sung Chun et al., "Toward 0.1µm Contact Hole Process by Using Water Soluble Organic Over-Coating Material (WASOOM); Resist Flow Technique (III); Study on WASOOM, Top Flare and Etch Characterization", Advances in Resist Technology and Processing XVIII, Proceedings of SPIE, Vol. 4345 (2001), pages 647-654.					
	CD	S. Satoh et al., "Electrical Properties of Bi ₄ Ti ₃ O ₁₂ Thin Films by MOCVD", Functional Devices Lab. Sharp Corp., with "Concise Explanation of the Relevance with Respect to Extended Abstracts (The 42nd Spring Meeting, 1995); The Japan Society of Applied Physics and Related Societies", 29p-D-3.					
EXAMINER				DATE CONSIDERED			

**Examiner: initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.*